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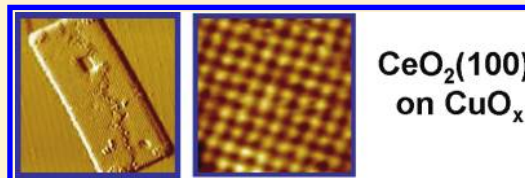
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CeO₂ ↔ CuO_x Interactions and the Controlled Assembly of CeO₂(111) and CeO₂(100) Nanoparticles on an Oxidized Cu(111) Substrate

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ABSTRACT: The catalytic performance of ceria-based heterogeneous catalysts in many chemical transformations (water–gas shift reaction, CO oxidation, alcohol synthesis from CO/CO₂ hydrogenation, etc.) is affected by the surface structure of the ceria. To control the performance of ceria-containing inverse catalysts, we devised a method to grow ceria nanoparticles (NPs) exposing exclusively either (111) or (100) surfaces and characterized their surface structures by scanning tunneling microscopy. When cerium is vapor-deposited on Cu(111) in a background of molecular O₂, only CeO₂(111) NPs grow. However, if the surface of Cu(111) is preoxidized with O₂ or NO₂ to form a rectangular copper oxide phase, probably Cu₄O₃(001), CeO₂(100) NPs grow on the oxide template instead. These experimental findings are interpreted using results of density functional calculations. The (100) surface of bulk ceria reconstructs to preserve charge neutrality. This is not necessary for CeO₂(100) NPs grown on Cu₄O₃(001), where the topmost oxygen layer of Cu₄O₃ is shared with the interfacial layer of cerium. After the CeO₂(100)/CuO_x/Cu(111) surfaces were exposed to CO, the copper oxide was reduced but the shape of the CeO₂(100) NPs remained intact. This opens the door for diverse applications in catalysis.



■ INTRODUCTION

Interest in oxide NPs supported on a metal surface has grown substantially in recent years,^{1–5} in part due to their unique reactivity and selectivity in catalysis. Cerium oxides supported on copper are an excellent example to showcase the catalytic properties of supported oxide NPs.^{6–10} Copper and cerium oxides are cost-effective materials widely used in catalytic applications. These two materials individually are not good catalysts for reactions such as CO oxidation or the water–gas shift (WGS). Our recent studies have shown that when ceria NPs are supported on Cu(111), this inverse model catalyst becomes very active for CO oxidation⁶ and the WGS.⁷ Meanwhile, newly designed inverse CeO_x/CuO_x powder nanocatalysts display a very high activity for the preferential oxidation of CO (PROX).⁸

To control the performance of ceria-containing inverse catalysts, we developed a new methodology that leads to the growth of ceria NPs which expose exclusively the (111) or (100) surface planes. Previously, (111)-terminated CeO₂ NPs were successfully synthesized and characterized on Cu(111).^{6,9,10} However, the (100) plane of CeO₂ is the least stable one and inherently the most reactive surface among the low index planes of ceria.^{11,12} Due to its polar character, the (100)-terminated ceria is intrinsically unstable and prone to reconstruction, imposing challenges for the synthesis of CeO₂(100) NPs. So far, progress has been made in the liquid-phase synthesis of ceria polyhedral NPs^{13,14} or quasi-2D nanosheets,¹⁵ which expose mostly (100) planes but also contain (111) and (110) planes. A problem is that catalysts prepared by the liquid-phase synthesis are difficult to characterize, especially regarding their surface structure and properties, which are essential for the understanding of active sites in catalysis.

In this paper, we report a method to grow crystalline CeO₂(100) NPs under ultrahigh vacuum (UHV) conditions and characterize their surface structures using scanning tunneling microscopy (STM).

■ EXPERIMENTAL AND COMPUTATIONAL METHODS

STM studies were conducted in a commercial Omicron variable-temperature STM system, equipped with surface cleaning facilities and an e-beam metal evaporator.¹⁶ The base pressure of the STM chamber was $<1 \times 10^{-10}$ mbar. The sample temperature was measured by a K-type thermocouple, which was installed on a linear motion feedthrough and pressed against the top of the sample surface. A resistive heater posited at the back of the sample could increase the sample temperature to 1000 K. Chemically etched W tips were used for imaging the surface. SPIP software (Image Metrology, Denmark) was used to process and analyze STM images. The Cu(111) single crystal was pretreated in a mixed H₂/Ar flow at 500 °C to remove any possible sulfur impurities from the bulk. After being transferred into UHV, the sample was cleaned by repeated cycles of Ar sputtering (1 keV, 40 min) and annealing (900 K, 10 min). CO gas was cleaned using a trap of liquid N₂ prior to the reduction of the Cu₂O surface. Ce atoms were evaporated by e-beam heating Ce foils (>99.9% purity, Alfa) housed in a Ta crucible.⁶

Periodic density functional theory (DFT) calculations were conducted using the Vienna ab initio simulation package (VASP)^{17,18} with projector augmented wave (PAW)¹⁹ potentials and the

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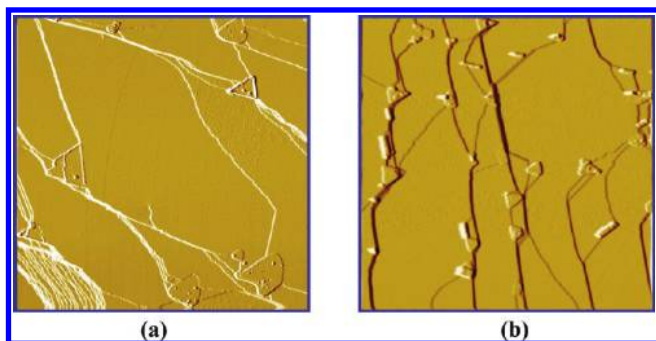


Figure 1. STM images of supported CeO_2 NPs prepared by Ce deposition in 5×10^{-7} mbar of O_2 at (a) 650 K and (b) 500 K, followed by annealing in 5×10^{-7} mbar of O_2 at 650 K. Both images are shown in the derivative mode. Image sizes are $500 \times 500 \text{ nm}^2$.

Perdew–Wang (PW91)²⁰ exchange–correlation functional. All calculations were carried out with a 400 eV kinetic energy cutoff for a plane wave basis set. Monkhorst–Pack²¹ meshes with $(3 \times 3 \times 3)$ and $(3 \times 3 \times 1)$ k -points were utilized for bulk and surface calculations, respectively. The flat $\text{Cu}(111)$ surface ($a_0 = 3.634 \text{ \AA}$) was simulated by a four-layer $p(3 \times 3)$ slab model with a vacuum space of 20 \AA , and one CeO_2 -like O–Ce–O layer (four Ce ions and eight O ions) was deposited on $\text{Cu}(111)$ to model $\text{CeO}_2/\text{Cu}(111)$. Cu_4O_3 has a $I4_1/amd$ structure with lattice parameters of $a = b = 5.875 \text{ \AA}$ and $c = 9.860 \text{ \AA}$, which are in good agreement with the experimental values ($a = b = 5.822 \text{ \AA}$ and $c = 9.844 \text{ \AA}$).²² The $\text{Cu}_4\text{O}_3(001)$ surface was simulated by an eight-layer $p(1 \times 1)$ slab model with a vacuum space of 20 \AA , and one CeO_2 -like O–Ce–O layer (two Ce ions and four O ions) was deposited on $\text{Cu}_4\text{O}_3(001)$ to model $\text{CeO}_2/\text{Cu}(111)$. In addition, to estimate the lattice mismatch of the CeO_2 -like structure on $\text{Cu}(111)$ and $\text{Cu}_4\text{O}_3(001)$, we also optimized bulk CeO_2 ($a_0 = 5.451 \text{ \AA}$). For surface calculations, the bottom two and four layers of the Cu and Cu_4O_3 surfaces, respectively, were fixed at the lattice position, while the other atoms, including the CeO_2 -like surface, were fully relaxed. The formation energy of the CeO_2 -like structure is calculated according to $E_f = E[\text{CeO}_2/\text{surf}] - nE[\text{Ce}] - 2nE[\text{O}_2]/2 - E[\text{surf}]$, where $E[\text{CeO}_2/\text{surf}]$, $E[\text{Ce}]$, $E[\text{O}_2]$, and $E[\text{surf}]$ are the energies of a deposited CeO_2 -like structure on a surface, the Ce atom, oxygen in the triplet state, and a surface ($\text{Cu}(111)$ or $\text{Cu}_4\text{O}_3(001)$) and n is the number of Ce atoms. Similar to the previous study,²³ the energy of the Ce atom was obtained from its bulk structure. Spin polarization calculations were used, and DFT + U with $U_{\text{eff}} = 4.5 \text{ eV}$ for Ce⁷ was utilized.

RESULTS AND DISCUSSION

Figure 1a shows ceria NPs exposing the highly stable (111) surface plane which were synthesized via the evaporation of Ce atoms in 5×10^{-7} mbar of O_2 onto the $\text{Cu}(111)$ surface held at 650 K. According to X-ray photoelectron spectroscopy (XPS) measurements, the as-grown ceria NPs are fully oxidized⁶ and exhibit overlapping moiré patterns due to the oxidation of $\text{Cu}(111)$ and the formation of an interfacial $\text{Cu}_2\text{O}(111)$ -like layer between $\text{Cu}(111)$ and $\text{CeO}_2(111)$.^{6,16} Interaction of CO with the $\text{CeO}_2/\text{Cu}_2\text{O}$ sample at temperatures above 650 K leads to its reduction and a loss of moiré patterns.⁶ Two types of ceria NPs were observed to grow on the copper surface when the growth temperature was lowered to $\sim 500 \text{ K}$ and annealed at

650 K in O_2 . As Figure 1b shows the ceria NPs exhibit two shapes: triangular and rectangular. The triangular-shaped ceria (t-ceria) islands display the (111) surface structure, whereas the rectangular-shaped ceria NPs (r-ceria) exhibit a square lattice. The growth of t-ceria NPs is anticipated since (a) the (111) face is the most stable surface of CeO_2 and (b) the hexagonal symmetry of $\text{CeO}_2(111)$ is matched by those of $\text{Cu}(111)$ and $\text{Cu}_2\text{O}(111)$. Is the r-ceria a metastable phase appearing at intermediate temperatures? The surface of Figure 1b was further annealed at higher temperatures (650–750 K). Neither a shape change nor a structural transition of r-ceria NPs was observed, ruling out the possibility of r-ceria being a kinetically trapped phase. Furthermore, XPS showed that the Ce atoms in these structures were fully oxidized.

The growth of crystalline NPs on a single crystal surface depends on many parameters, including the lattice mismatch, crystal orientation, growth temperature, and interfacial energy. A surface with domains of different symmetries should direct the growth of NPs to different interfacial structures. The oxidized $\text{Cu}(111)$ surface can provide such a substrate. Surface oxidation of $\text{Cu}(111)$ using molecular O_2 under vacuum conditions (10^{-8} – 10^{-6} mbar) leads to the formation of the so-called “44” and “29” structures²⁴ of a $\text{Cu}_2\text{O}(111)$ -like oxide monolayer. As described in our recent paper,⁶ supported ceria NPs can dissociate O_2 , with atomic oxygen spilling over to the $\text{Cu}(111)$ substrate and forming different copper oxide domains whose structure is dependent on the distance from the ceria NP. The presence of ceria NPs promotes the oxidation of $\text{Cu}(111)$ beyond the 44 and 29 surface oxides and leads to the formation of a novel 3D phase of copper oxide with a rectangular unit cell.⁶ The novel oxide phase, termed a rectangular copper oxide, has a symmetry matching that of r-ceria and might serve as the substrate for the growth of r-ceria NPs.

Is the growth of r-ceria NPs solely a consequence of the formation of a rectangular copper oxide template? To test this hypothesis, we attempted to grow exclusively r-ceria NPs. First, the 44- Cu_2O surface oxide was formed by oxidizing the $\text{Cu}(111)$ substrate in 5×10^{-7} mbar of O_2 at 550 K.²⁵ Next, ceria clusters were deposited on the surface of the 44- Cu_2O surface oxide at room temperature, as shown by Figure 2a. The as-deposited ceria clusters are dispersed on the Cu_2O surface with a narrow size distribution (0.6–2.0 nm in radius). At temperatures below 550 K, ceria clusters have limited mobility on the Cu_2O surface oxide and do not sinter. The surface was then annealed in 5×10^{-7} mbar of O_2 at 400, 450, 500, and 550 K and held for 10 min at each temperature. Parts b and c of Figure 2 show the results of the sequential annealing steps. The rows of copper oxide are decorated by small ceria clusters and form domains rotated by 45° or 90° ; in contrast, the 44- Cu_2O surface oxide domains are rotated 60° or 120° . Parts b and c of Figure 2 also illustrate that the continuing surface oxidation is accompanied by shrinking of ceria clusters. These ceria clusters start to sinter at temperature above 650 K. After annealing to 750 K, most ceria clusters move to step edges, forming r-ceria NPs (Figure 2d).

The structure and morphology of r-ceria NPs are displayed in Figure 3. The apparent heights of the r-ceria NPs are measured as multiples of $\sim 0.30 \text{ nm}$. Shown in Figure 3a is a multilayer r-ceria NP with a lattice spacing of 0.56 nm. Such lattice spacing is observed for all multilayer r-ceria NPs (>20 NPs were examined). Ceria NPs of monolayer thickness ($\sim 0.30 \text{ nm}$) have a smaller square lattice of 0.40 nm that could be observed under aggressive scanning conditions (i.e., $<1.0 \text{ V}$ sample bias, Figure 3b). The apparent height and the square lattice with 0.40 nm spacing

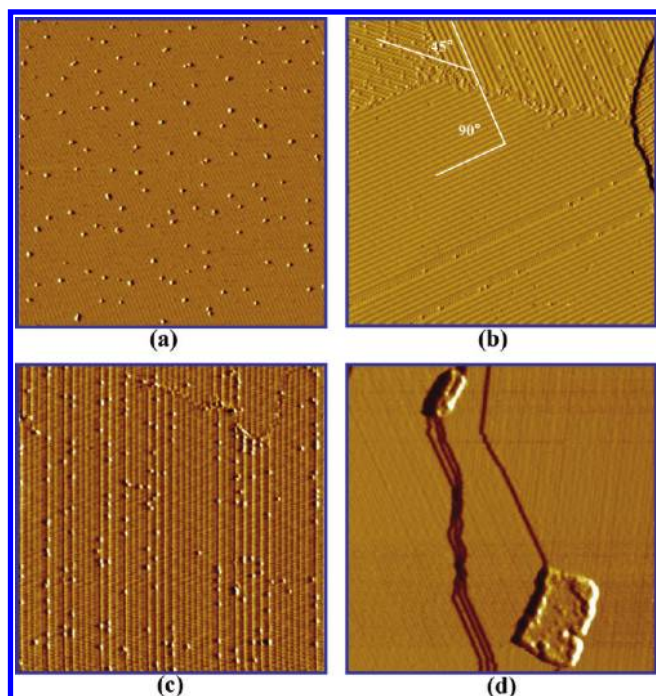


Figure 2. STM images for the synthesis of rectangular-shaped ceria NPs on Cu(111): (a) ceria grown by evaporating cerium in 5×10^{-7} mbar of O_2 at 300 K onto a $44\text{-Cu}_2\text{O}$ surface oxide, which was formed by oxidizing the Cu(111) substrate in 5×10^{-7} mbar of O_2 at 550 K; (b, c) surface of (a) after being heated in 5×10^{-7} mbar of O_2 at 400, 450, 500, and 550 K for 10 min, respectively; (d) surface of (c) after being annealed in 5×10^{-7} mbar of O_2 at 750 K for 10 min. All images are shown in the derivative mode to enhance the contrast of surface features. Image sizes are (a, d) $200 \times 200 \text{ nm}^2$ and (b, c) $100 \times 100 \text{ nm}^2$.

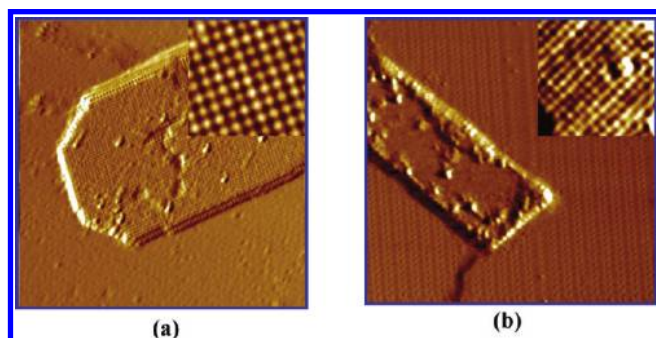


Figure 3. STM images of the structure of the rectangular-shaped ceria NPs. The atomic structure of each ceria NP is zoomed in the inset. Both large-scale images are shown in the derivative mode. Image sizes are (a) $50 \times 50 \text{ nm}^2$ and (b) $40 \times 40 \text{ nm}^2$. Both insets are $5 \times 5 \text{ nm}^2$. Scanning conditions are (a) $V_s = 1.6 \text{ V}$ and $I_t = 0.1 \text{ nA}$ (same for the inset) and (b) $V_s = 1.0 \text{ V}$ and $I_t = 0.1 \text{ nA}$ (inset: $V_s = 0.8 \text{ V}$, $I_t = 0.1 \text{ nA}$).

closely match those of the unreconstructed $\text{CeO}_2(100)$ surface. Therefore, we assign the r-ceria NPs as $\text{CeO}_2(100)$ NPs. The 0.56 nm spacing observed in the STM images of multilayer r-ceria NPs might be due to the surface relaxation and will be discussed later.

We have demonstrated that ceria-promoted copper oxidation and the formation of rectangular copper oxides are the key to the formation of $\text{CeO}_2(100)$ NPs. For the purpose of the controlled synthesis of $\text{CeO}_2(100)$ NPs, a simpler strategy is to facilitate the

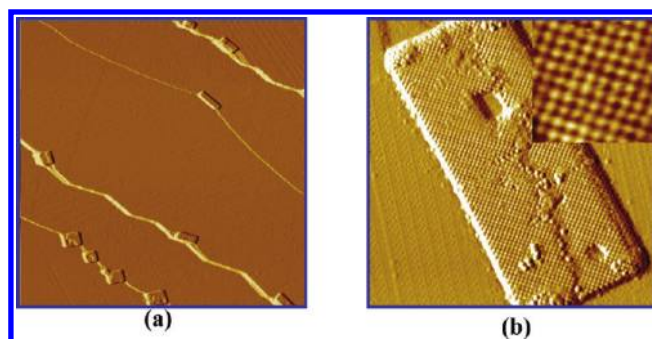


Figure 4. STM images of $\text{CeO}_2(100)$ NPs prepared by Ce deposition in 5×10^{-7} mbar of O_2 at 650 K on a copper oxide surface, formed by oxidizing Cu(111) with NO_2 at 600 K. Both large-scale images are shown in the derivative mode. Image sizes are (a) $500 \times 500 \text{ nm}^2$ and (b) $40 \times 40 \text{ nm}^2$.

oxidation of Cu(111) by using atomic oxygen sources.²⁶ In our study, we used NO_2 to induce the rectangular copper oxide growth on Cu(111). After a dose of 11 L of NO_2 at 600 K, the rectangular copper oxide phase was formed on the Cu(111) surface. Subsequently, ceria NPs were grown on the rectangular copper oxide surface by evaporating Ce atoms in 5×10^{-7} mbar of O_2 at 650 K. As shown in Figure 4, all ceria NPs are rectangular-shaped (Figure 4a) and the ceria NP exhibits a square lattice with a lattice spacing of 0.56 nm (Figure 4b). Note that both types of ceria NPs, $\text{CeO}_2(111)$ and $\text{CeO}_2(100)$, exhibit two kinds of edges, one with higher brightness than the NP surface (see Figures 1a and 3b) and the other with the same brightness as the NP surface (see Figures 1a and 4b). A similar phenomenon was seen on MoS_2 NPs and interpreted as the presence of the metallic brim states.²⁷

The structural details of the rectangular copper oxide cannot be resolved using solely STM data. Both XPS and STM studies suggest the rectangular copper oxide has a higher oxygen concentration than the Cu_2O surface oxide. Our previous study²⁸ has shown the presence of an intermediate phase, Cu_4O_3 , during the phase transition between Cu_2O and CuO . The (001) surface of Cu_4O_3 , which is thermodynamically favorable, exhibits a pseudo square lattice and could serve as the substrate for the growth of $\text{CeO}_2(100)$. Here, we assume the observed rectangular copper oxide phase originates from the $\text{Cu}_4\text{O}_3(001)$ layers, which could be distorted on Cu(111) due to the interfacial strain and exhibit a rectangular unit cell larger than that of the unsupported $\text{Cu}_4\text{O}_3(001)$.

We used DFT calculations to gain insight into the formation of r-ceria. To reduce the computational load, the (001)-terminated bulk Cu_4O_3 , instead of Cu(111)-supported $\text{Cu}_4\text{O}_3(001)$ layers, was used to build a CeO_2 layer in our DFT calculations. The structure of CeO_2 on Cu(111) was also computed as a comparison. Figure 5 displays the optimized geometries of stoichiometric CeO_2 deposited on Cu(111) and $\text{Cu}_4\text{O}_3(001)$. Our calculations show that $\text{Cu}_4\text{O}_3(001)$ allows the growth of $\text{CeO}_2(100)$, while on Cu(111), $\text{CeO}_2(111)$ is the most stable structure. The formation energy of $\text{CeO}_2(111)$ on Cu(111) is -10.8 J/m^2 , slightly lower than that of $\text{CeO}_2(100)$ on $\text{Cu}_4\text{O}_3(001)$, -8.9 J/m^2 . Therefore, the growth of $\text{CeO}_2(100)$ on $\text{Cu}_4\text{O}_3(001)$ is thermodynamically favorable and has a stability comparable to that of $\text{CeO}_2(111)/\text{Cu(111)}$.

Our calculations also show, unlike the growth of CeO_2 on Cu(111), CeO_2 grows as a pseudomorphic layer on

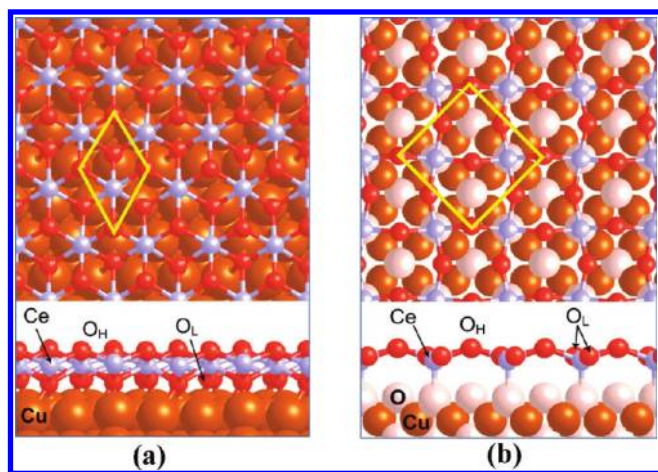


Figure 5. Top and side views of DFT-optimized CeO_2 structures on (a) $\text{Cu}(111)$ and (b) $\text{Cu}_4\text{O}_3(001)$. The rhombus and rectangle in yellow represent unit cells. Ce and O atoms on CeO_2 are in light blue and in red, respectively, while Cu and O atoms on the substrates are in orange and in light pink, respectively.

$\text{Cu}_4\text{O}_3(001)$; i.e., the lattice of $\text{CeO}_2(100)$ is expanded to adapt to the lattice of $\text{Cu}_4\text{O}_3(001)$. The distance between nearest Ce cations of the relaxed CeO_2 layer on $\text{Cu}_4\text{O}_3(001)$ is computed at 0.416 nm, 8.1% larger than that of bulk CeO_2 (0.385 nm). The strain introduced by the expansion of the CeO_2 lattice is relaxed through the lateral displacements of oxygen atoms in the CeO_2 layer, as shown in Figure 5b. In the case of the $\text{CeO}_2(100)$ NPs, such a large expansion probably does not occur due to local relaxation. The lateral displacements of oxygen atoms are not obvious in our STM images. In STM, since the measurement was conducted at positive sample bias, the STM contrast presumably originates from the 4f states of Ce cations. Our STM measurement gives the Ce–Ce distance at 0.40 nm in the monolayer $\text{CeO}_2(100)$, which also suggests some expansion of the $\text{CeO}_2(100)$ lattice. Thus, the difference in lattice parameters obtained from STM and DFT might be due to the fact that STM measurements are conducted on $\text{CeO}_2(100)$ NPs while the calculation is performed with a full $\text{CeO}_2(100)$ layer. For large coverages of ceria, we observed three-dimensional growth instead of a single full layer of $\text{CeO}_2(100)$ wetting the underlying copper oxide.

In the case of multilayer $\text{CeO}_2(100)$ NPs, the observed lattice spacing of 0.56 nm might be caused by a strong surface relaxation. Note that a previous STM study²⁹ on the bulk $\text{CeO}_2(100)$ surface shows a variety of surface reconstructions. CeO_2 , along the (001) direction, is stacked by alternating planes of cerium cations and oxygen anions. The charge density of the cerium plane equals that of the oxygen plane (but with opposite sign). A nonzero charge dipole persists for $\text{CeO}_2(100)$ when the bulk is terminated by oxygen at both sides of the slab. Consequently, the surface of $\text{CeO}_2(100)$ reconstructs to preserve charge neutrality. In $\text{CeO}_2(100)$ NPs grown on $\text{Cu}_4\text{O}_3(001)$, the topmost oxygen layer of Cu_4O_3 is shared with the interfacial layer of cerium. In the case of the $\text{CeO}_2(100)$ monolayer, the added layer of cerium is even with the layer of oxygen and charges cancel out at the surface. Therefore, the surface relaxation of a $\text{CeO}_2(100)$ monolayer on $\text{Cu}_4\text{O}_3(001)$ is minimal compared with that of multilayer/bulk $\text{CeO}_2(100)$. As the surface electrostatic potential increases with the thickness of the $\text{CeO}_2(100)$ oxide film,³ we

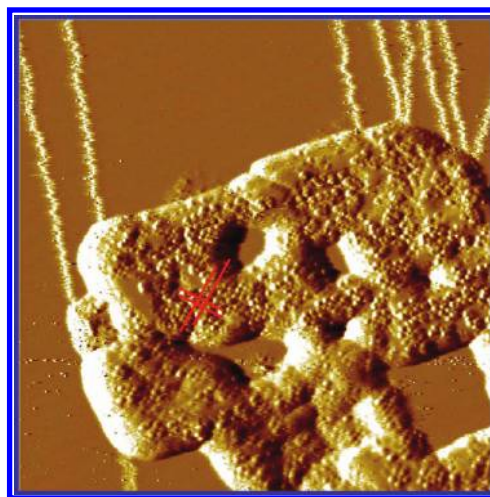


Figure 6. STM image of a sintered $\text{CeO}_2(100)$ NP after CO reduction. The surface was obtained by reducing the surface of Figure 2d in 5×10^{-6} mbar of CO at 750 K for 2 h. The image size is $50 \times 50 \text{ nm}^2$. The red lines mark the position of ceria clusters on the surface of the $\text{CeO}_2(100)$ NP.

expect the surface relaxation of multilayer $\text{CeO}_2(100)$ NPs is more severe and might involve the displacements of top-layer Ce atoms. Within this hypothesis, the 0.56 nm square lattice observed in STM could suggest a $(\sqrt{2} \times \sqrt{2})$ reconstruction of Ce cations in the top layer. In other words, Ce atoms are relaxed vertically in such a way that only half of the surface Ce atoms are resolved in STM.

The removal of the $\text{Cu}_4\text{O}_3(001)$ substrate could destabilize the surface of $\text{CeO}_2(100)$. We used the sample of $\text{CeO}_2(100)$ NPs prepared in Figure 2 and reduced it in 5×10^{-6} mbar of CO at 750 K for 2 h to fully remove the copper oxides present on $\text{Cu}(111)$.¹⁶ Figure 6 shows that the $\text{CeO}_2(100)$ NPs agglomerate and form large rectangular particles. The ripened CeO_2 NP displays a roughened surface, which in part might be due to the presumed absence of an interfacial copper oxide layer that otherwise stabilizes $\text{CeO}_2(100)$. Also some oxygen could be removed from ceria according to XPS measurements. Figure 6 also shows that small clusters at the surface of the ripened NP remain ordered in a square lattice, as marked by red lines. The lattice of clusters have a spacing of $\sim 0.5\text{--}0.6$ nm, matching the lattice periodicity observed on multilayer $\text{CeO}_2(100)$ NPs and suggesting that the crystal structure and orientation of $\text{CeO}_2(100)$ NPs remain intact after CO reduction. Note that the reduction kinetics of surface copper oxides is highly dependent on the oxidation conditions used to prepare the $\text{CeO}_2(100)$ NPs. We also tried to reduce the sample of $\text{CeO}_2(100)$ NPs prepared in Figure 3. Using the same conditions, i.e., in 5×10^{-6} mbar of CO at 750 K for 2 h, the surface of $\text{CeO}_2(100)$ NPs remained unchanged, except for a few vacancies observed in the surface of rectangular copper oxides.

SUMMARY AND CONCLUSIONS

In conclusion, we have described preparation procedures on how to grow exclusively either $\text{CeO}_2(111)$ or $\text{CeO}_2(100)$ NPs on $\text{Cu}(111)$, providing a better way to control the performance of ceria-containing inverse catalysts. In traditional approaches for growing oxides on a metal surface, the goal is to have initially a metal substrate that is chemically inert and thermally stable.³ Our

study, on the other hand, illustrates that a reactive substrate provides the opportunity and versatility for the controlled synthesis of multiple facets and the growth of less stable/more reactive NPs. The growth of $\text{CeO}_2(100)$ NPs is induced by the formation of a rectangular copper oxide phase on $\text{Cu}(111)$. In contact with the rectangular copper oxide face, presumably $\text{Cu}_4\text{O}_3(001)$, Ce atoms are constrained in a square configuration and forced to adopt a geometry that is not stable as a termination for bulk ceria. DFT calculations show that the formation energy of $\text{CeO}_2(111)$ on $\text{Cu}(111)$ is -10.8 J/m^2 , slightly lower than that of $\text{CeO}_2(100)$ on $\text{Cu}_4\text{O}_3(001)$, -8.9 J/m^2 . The growth of $\text{CeO}_2(100)$ on $\text{Cu}_4\text{O}_3(001)$ is thermodynamically favorable and has a stability comparable to that of $\text{CeO}_2(111)/\text{Cu}(111)$. Upon reduction of the underlying copper oxide, the shape of the $\text{CeO}_2(100)$ NPs did not change. The controlled growth of $\text{CeO}_2(100)$ NPs opens the door for enhanced chemical activity and applications in important processes (CO oxidation, PROX, WGS, synthesis of alcohols from CO/CO_2 hydrogenation, NO reduction, etc.) catalyzed by copper–ceria catalysts.

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